

	Hit s	Search Text	DBs
36	86	<p>(projection near9 (optical or \$lithograph\$4) near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus or chamber)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or platen)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (((nitrogen or nitrous or nitric) near16 (oxide or dioxide)) or "NO.sub.2") or ((fluoroalkane or fluorin\$4) near12 (alkane or methane or ethane))))</p>	US-PPGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	<b>Hit s</b>	<b>Search Text</b>	<b>DBs</b>
37	5	<p>(projection near9 (optical or \$5lithograph\$4) near9 (system or apparatus) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus or chamber)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or platen)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV or laser)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (((nitrogen or nitrous or nitric) near16 (oxide or dioxide)) or "NO.<sub>2</sub>") or ((fluoroalkane or fluorin\$4) near12 (alkane or methane or ethane))) same (remov\$4 or rid or eliminat\$4) same (contaminant or organic or residu\$3))</p>	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB